## Bifunctional Complementary Type Ferroelectric Memory Circuit with both P- and N-channel MoTe<sub>2</sub>

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Two dimensional (2D) semiconductors such as transition metal dichalcogenides (TMDs) have extensively been studied, resultantly displaying their great potentials in many devices and applications [1-5]. In the present work, we report ferroelectric nonvolatile memory (FeNVM) field effect transistors (FETs) using p-channel MoTe<sub>2</sub> and organic P(VDF-TrFE) polymer, and furthermore a complementary type memory cell is demonstrated coupling p- and n-channel MoTe<sub>2</sub> FETs. A top-gate p-FET with P(VDF-TrFE) and a bottomgate n-FET with Al<sub>2</sub>O<sub>3</sub> dielectric are integrated as one cell. Such a complementary type cell is in fact more desirable research path in respect of power consumption but rare to find in 2D-based memory reports. We select MoTe<sub>2</sub> among many other 2D semiconductors, because p-type MoTe<sub>2</sub>-based ferroelectric memory is not reported yet, and also because it is relatively easy to obtain both p- and n-channel from the homogeneous MoTe<sub>2</sub>. The integrated device operates as a complementary metal oxide semiconductor (CMOS) inverter in a small voltage range from 0 to ~2.5 V as well, but primarily works as a ferroelectric nonvolatile memory circuit when p-channel with top P(VDF-TrFE) ferroelectric polymer is biased with high voltages over the coercive electric field (E<sub>c</sub>) of the polymer. The bottom-gate n-channel transistor operates as a switching device in the FeNVM cell, allowing voltage output signals during device operations. We conclude that our complementary type FeNVM cell is practical and novel enough to report as a first demonstration based on MoTe<sub>2</sub>.

## References

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## Figures





Figure 2: The current-voltage characteristics of p- and n-type MoTe2 transistors and the retention curve of the memory cell



Figure 3: The voltage transfer curve and gain (inset power consumption) of the complementary type cell in CMOS operation regime.